Robust liquid metal collector mirror for EUV and soft X-ray plasma sources

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Overview

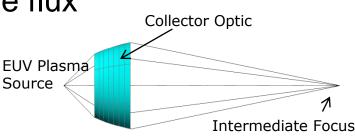
- Motivation
- First Prototypes (Cone + Flat)
- Current Prototypes (Cylinder + Ellipsoid)
- Zemax Modelling
- Focused EUV First Results
- Lifetime Monitoring
- Planned Work

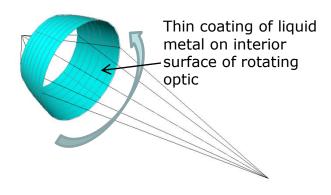


Motivation

- EUV Sources for Metrology
 - > Simple collector \longrightarrow ~10⁴ more flux
 - Requires atomically flat mirror
 - Sn Plasma debris + fast ions
 - Lifetime issues
- Liquid metal coated mirror
 Sn based alloy
 Relatively long lifetime
 No debris mitigation





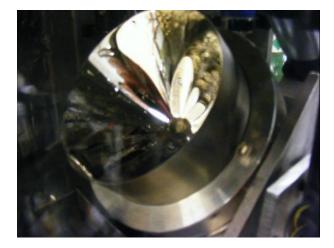


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First Prototypes

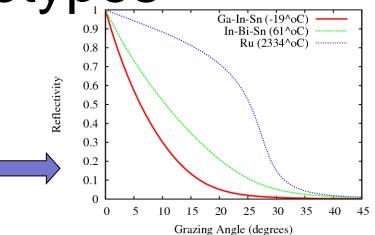
- Established coating mechanism on rotating optic
 - ➢ GalnSn alloy ; Melting pt -19⁰C
 - > Theoretical R v θ at 13.5 nm (92eV)

(from <u>http://henke.lbl.gov/optical_constants/mirror2.html</u>)



Cone: Dia: 100mm

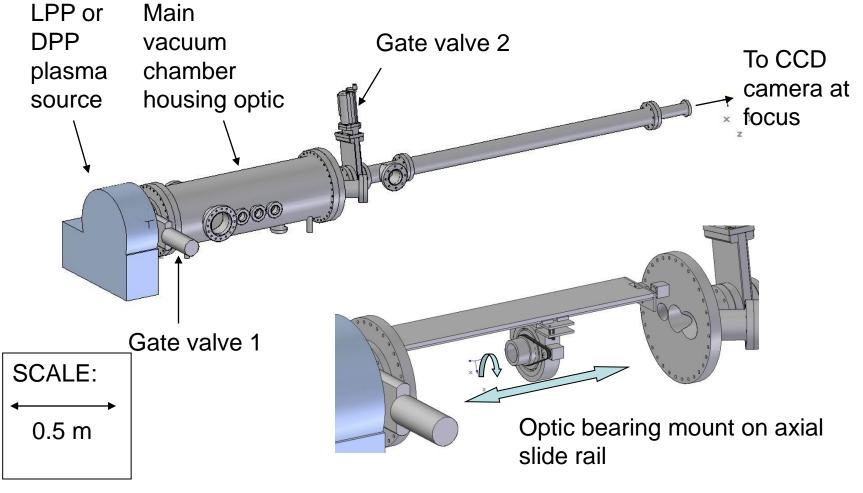






Plane: Dia: 100mm

Focusing EUV: Exp. Design





EUV Testing: Initial Setup

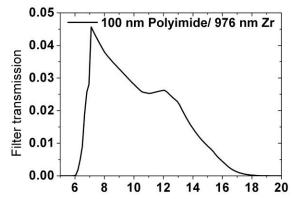
□ Sn LPP source

□Optic: Cylinder shell 80 mm x 55 mm (LxDia)

100 nm Poly/976 nm Zr EUV filter

CCD camera: Princeton Instruments PI-SX, 1024x1024, 13 μm pixels.



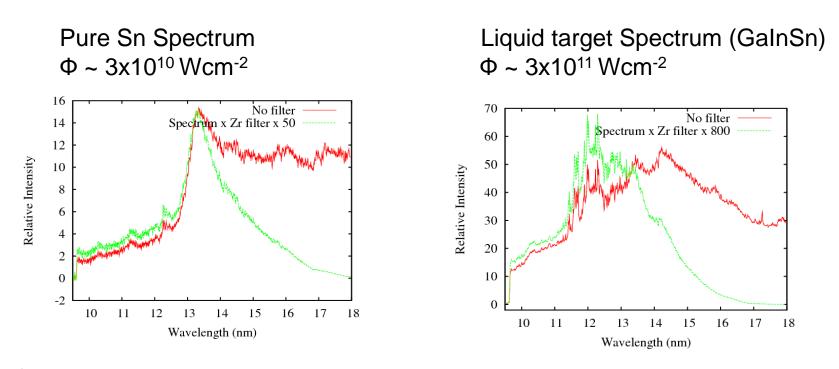






Source Spectra

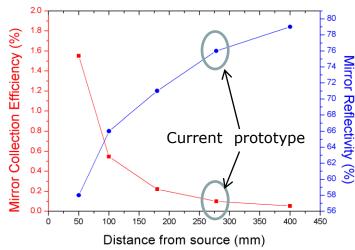
Jenoptik Espec grazing incidence spectrograph





Zemax Modelling

- Cylinder + Ellipsoid performance modelled
- Optimization of Ellipsoid for typical DPP source

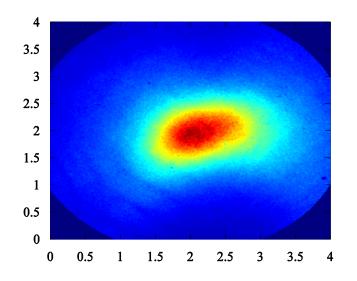


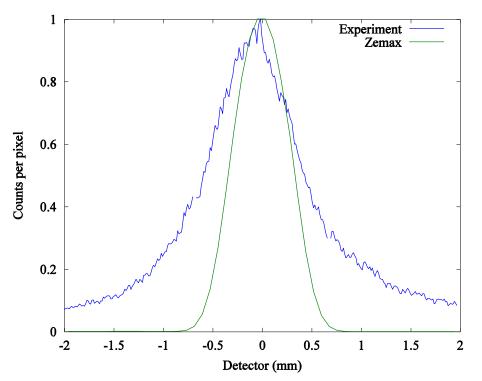
	Present Collector	Optimized Collector I	Optimized Collector II
In-band Power at source (W)	11.2	11.2	11.2
Source radius or FWHM (mm)	0.345	0.345	0.345
Source to mirror distance (mm)	278	200	25
Magnification	13.6	3.2	2.6
Average Reflectivity (%)	78	67	18
Power Density at Image (mW/mm ²)	0.4	14.4	151.9
Power Density No Collector (mW/mm ²)	0.0002	0.0024	0.029



Focused EUV – First Results

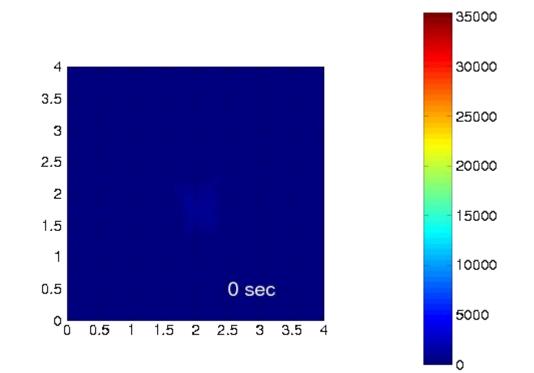
• Ellipsoid Section





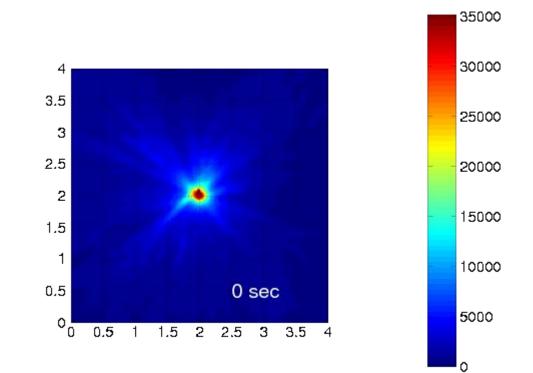


Mirror Start-up



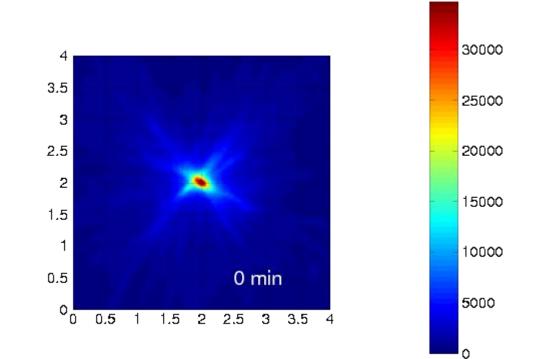


Mirror Running





Mirror Stopping





Lifetime Testing

- 20 W LPP Plasma
- Plasma to mirror distance = 200 mm

# Pulses (x1000)	# EUV Photons collected	Image fwhm (µm)
0	3.08 x 10^6	290
200	2.78 x 10^6	299
400	3.11 x 10^6	292
600	3.01 x 10^6	302
800	3.05 x 10^6	286



Ongoing Work

- Characterise EUV Source
- Optically characterise ellipsoid figure error
- Zemax Application specific optimum mirror shapes
- Long term operation in front of commercial DPP or LPP source



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